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ABSTRACT OF THE DISCLOSURE

A method for inspecting a photomask, comprising
generating a laser beam, changing a phase of the laser
beam to smooth the brightness distribution of the laser
beam, applying the smoothed laser beam to the photomask,
5 acquiring an image of the photomask using a sensor
while the laser beam and the photomask are relatively
moved, examining the image of the photomask for
a defect of the mask-pattern of the photomask.

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